## SEP 2 2 2003 &

RESPONSE UNDER 37 C.F.R. 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 2829

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

4/26/9 OK-to entr

Appl. No.

10/099,641

Applicants:

Wilbur G. Catabay and Richard Schinella

Filed:

March 15, 2002

Title

LOW K DIELECTRIC COMPOSITE LAYER FOR INTEGRATED

CIRCUIT STRUCTURE WHICH PROVIDES VOID-FREELOW K
DIELECTRIC MATERIAL BETWEEN METAL LINES WHILE

MITIGATING VIA POISONING

Grp./ A.U. :

2829

Examiner

Lisa A. Kilday

Docket No. :

99-102/1D

## **CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

September 16, 2003

(Date of Deposit)

John P. Taylor, Reg. No. 22,369

September 16, 2003

Date of Signature

## RESPONSE TO FINAL REJECTION

Honorable Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Date: September 16, 2003

In response to the Final Rejection mailed July 16, 2003, please amend the application as follows: